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(54) Title: METHOD OF POLISHING NICKEL-PHOSPHOROUS

(57) Abstract: The invention is directed to a method of chemically-mechanically polishing a a surface of a substrate, comprising contacting a surface of a substrate comprising nickel-phosphorous with a chemical-mechanical polishing composition comprising wet-process silica, an agent that oxidizes nickel-phosphorous, and an aminopolycarboxylic acid, wherein the polishing composition has a pH of 1 to 5, and abrading at least a portion of the nickel-phosphorous to polish the substrate.

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